

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	(electroplating and (copper or cu) and semiconductor and (defect near3 reducing near3 agent\$3) and (benzyl near3 chloride) and (hydroxyethyl near3 polyethylenimine)).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2007/10/19 16:30